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Antechamber type vacuum chamber coated with non-evaporable getter films

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To coat the inner surface of antechamber type vacuum chamber for Hefei Advanced Light Facility (HALF) with nonevaporable getter material (NEG), a dedicated magnetron sputtering setup has been prepared at National Synchrotron Radiation Laboratory (NSRL). The magnetron sputtering device and the coating method are introduced in this paper. The properties of the films were tested. This coating method has been proved to be feasible and ensures the stability of the discharge and the reliability of the NEG film quality, which satisfy the stringent engineering requirements of HALF. This study may also offer a reference for similar vacuum chamber coating applications.

Footnotes

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